

METHOD FOR FABRICATING AN INTERFERENCE DISPLAY UNIT

Abstract of the Disclosure

A method for fabricating an interference display unit is disclosed. A first wall and a sacrificial layer are formed in order on a substrate and an opening is formed in the first wall and the sacrificial layer. A first photoresist layer is spin-coated on the sacrificial layer and fills the openings. A post having a first arm is formed through patterning the first photoresist layer. At least a second photoresist is formed by spin-coating. A second arm is formed on the first arm through patterning the second photoresist layer. A second wall is formed on the sacrificial layer and posts. The first and the second arms' stress is released through a thermal process. The position of the arm is shifted and the distance between the first wall and the second wall is therefore defined. Finally, the sacrificial layer is removed.

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